Client's ref.: 91080 Our ref: 0593-10033us/final/yyhsu/Steve

5

10

ABSTRACT OF THE DISCLOSURE

The invention provides a method for forming a bottle-shaped trench. A semiconductor substrate having a pad stack layer and a trench formed thereon is provided. Sidewall protective layers are then formed on the upper sidewalls of the trench. A masking layer is formed at the bottom of the trench, followed by wet etching to remove the semiconductor substrate not covered by the sidewall protective layers thus forming a bottle-shaped trench. Finally, the masking layer is removed.